

	Hits	Search Text	DBs
68	14	((EUV or UV or VUV or DUV or X\$2ray) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5 or pattern) near19 strip\$4 near12 (remov\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
69	46	((EUV or UV or VUV or DUV or X\$2ray) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5 or pattern) near19 strip\$4) and ((resist or photoresist) near12 (mask or pattern) near16 etch\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
70	41	((EUV or UV or VUV or DUV or X\$2ray) near9 (irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5 or pattern) near19 strip\$4) and ((resist or photoresist) near4 (mask or pattern) near16 etch\$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB